



## Correction: Droplet microfluidics: fundamentals and its advanced applications

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Correction for 'Droplet microfluidics: fundamentals and its advanced applications' by Somayeh Sohrabi et al., *RSC Adv.*, 2020, 10, 27560–27574, DOI: 10.1039/D0RA04566G.

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In addition, the authors regret that incorrect reference numbers were given in Table 1 of the original article. The corrected table and references are shown below.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

**Table 1** Size and frequency distributions for various droplet generation systems

	Geometry and material	Continuous phase	Size/ $\mu\text{m}$	Frequency/ Hz	Ref. in original article reference list	Ref. in this Correction
Water in oil	Channel array in silicon	Kerosene with monolaurate	21	~5300 (est.)	—	1
	T-junction in acrylated urethane	Decane, tetradecane, and hexadecane with Span 80	10 to 35	20 to 80	—	2
	T-junction in PMMA	High oleic sunflower oil	100 to 350	10 to 2500	—	3
	T-junction in PDMS	C <sub>14</sub> F <sub>12</sub> with (C <sub>6</sub> F <sub>13</sub> )(CH <sub>2</sub> ) <sub>2</sub> OH	7.5 nl (plug flow)	2	55	4
	Shear-focusing in PDMS	Oleic acid	13 to 35 (satellites <100 nm)	15–100	49	5
Oil in water	Channel array in silicon	Water with SDS	22.5	~5300 (est.)	—	1
	Sheath flow in glass capillary	Water with SDS	2 to 200	100 to 10 000	—	6
Gas in liquid	Flow-focusing in PDMS	Water with Tween 20	10 to 1000	>100 000	—	7
	Shear-focusing in PDMS	Water with phospholipids	5 to 50	>1 000 000	—	8
Liquid in air	DEP on hydrophobic insulator	Air	10 pl	~8 (est.)	57	9
	EWOD on hydrophobic insulator	Air	~700 nl	~1 (est.)	28	10



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